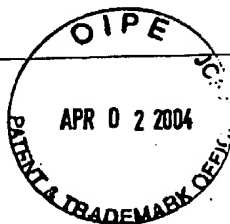


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**INFORMATION DISCLOSURE STATEMENT  
BY APPLICANT**

Applicant: BASELMANS et al.

Appln. No.: 09/905,198

Filing Date: July 16, 2001

Date: April 2, 2004

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Examiner: Mohamedulla

Group Art Unit: 3046

OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

SRM	AR	Peter D. Buck et al., "Phase Shift Mask Applications," Proceedings of SPIE – The International Society for Optical Engineering, Optical/Laser Microlithography IV, 6-8 March 1991, Coversheet + 9 pages.				
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SRM	CR	Yong Liu et al., "Computer Aided Phase Shift Mask Design with Reduced Complexity," Department of Electrical Engineering and Computer Sciences, University of California at Berkeley, CA 94720, SPIE Vol. 1927 Optical/Laser Microlithography VI (1993) pp. 477-493.				
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\*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.